

16oct01 17:25:21 User015070 Session D6839.1
Sub account: ASMJP.100AUS-CSP

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****ABSTRACTS FOR JP 11176593, JP 521520 AND JP 9320799****

File 347:JAPIO OCT 1976-2001/JUN(UPDATED 011001)

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06235022 **Image available**

PLASMA PROCESSING APPARATUS AND MANUFACTURE OF OPTICAL PARTS

PUB. NO.: 11-176593 A]

PUBLISHED: July 02, 1999 (19990702)

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APPL. NO.: 09-343085 [JP 97343085]

FILED: December 12, 1997 (19971212)

ABSTRACT

PROBLEM TO BE SOLVED: To form a cover which is superior in in-plane uniformity with less local faults such as pin hole, and has superior covering characteristic by providing a face opposite to a processed body of microwave supply means as a non-flat face whose shape corresponding to a processed face of the processed body.

SOLUTION: When a thin film is formed at a spherical lens, a convex lens is first disposed and fixed so that a processed face is faced upward on a holder 104. Next, a holder 104 is risen by a driving mechanism 105, and a gap Tg between a processed body opposite face 106a and a processed face Wa of a dielectric plate 106 of a non-flat face consisting of a microwave transparent dielectric is set as a given value. Processing gas is introduced into a plasma process space A by a gas introducing port 103 via a gas supply passage 108, and the pressure in a vessel is maintained to a proper pressure by controlling a gas supply quantity or the like. Next, microwaves are supplied to a conductor flat plate antenna 111, gas plasma is generated, and a film with its high density and fine quality can be formed.